

What is claimed is:

1. An evaporation method, comprising:

providing a substrate, fixing the center of the substrate and rotating the substrate ;

defining a circular trace by the center of the substrate;

5 providing a heater;

providing a source supplying device, wherein the source supplying device
supplies an evaporation source to the heater along a supplying direction;

disposing the heater and the source supplying device under a point of the
circular trace and adjusting the supplying direction of the source supplying device for
10 paralleling the supplying direction and a tangential direction of the point of the circular
trace; and

heating the evaporation source by the heater for evaporation.

2. The evaporation method of claim 1, further comprising disposing a shelter
15 between the source supplying device and the substrate for defining an evaporation
region.

3. The evaporation method of claim 2, wherein a radius of the evaporation
region is substantially similar to that of the circular trace.

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4. The evaporation method of claim 1, wherein a rotational direction of the
substrate is clockwise.

5. The evaporation method of claim 1, wherein a rotational direction of the substrate is counterclockwise.

6. The evaporation method of claim 1, wherein the evaporation source is
5 aluminum or silver.

7. An evaporation apparatus for depositing a film on a substrate, the evaporation
apparatus comprising:

a rotator fixing the center of a substrate and rotating the substrate to define a
10 circular trace;

a heater, disposed under a point of the circular trace; and

a source supplying device, disposed over the heater, wherein the source
supplying device supplies an evaporation source to the heater along a supplying
direction and the supplying direction is parallel to a tangential direction of the circular
15 trace.

8. The evaporation apparatus of claim 7, further comprising a shelter disposed
between the source supplying device and the substrate for defining the evaporation
region, wherein the shelter has an opening for defining the evaporation region on the
20 substrate.

9. The evaporation apparatus of claim 8, wherein the opening is a circular
opening.

10. The evaporation apparatus of claim 9, wherein a radius of the evaporation region is substantially similar to that of the circular trace.

11. The evaporation apparatus of claim 7, wherein the evaporation source is
5 aluminum or silver.

12. The evaporation apparatus of claim 7, wherein a rotational direction of the substrate is clockwise.

10 13. The evaporation apparatus of claim 7, wherein a rotational direction of the substrate is counterclockwise.

14. The evaporation apparatus of claim 7, wherein the heater is a rectangular loading crucible.